

ABSTRACT OF THE DISCLOSURE

A positive type resist composition comprising: (A) a resin having a monocyclic or polycyclic alicyclic hydrocarbon structure, which increases the solubility in an alkali developing solution by the action of an acid; (B) a compound capable of generating an acid upon irradiation with an actinic ray or a radiation; and (C) an alkoxy alcohol as a solvent, wherein an alkoxy group and an alcoholic hydroxyl group are connected to each other via at least three carbons.